## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Hyun-Woo Kim et al.

Examiner: Amanda C. Walke

Serial No:

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For: METHOD OF FORMING AN UNDERLAYER OF A BI-LAYER RESIST

FILM AND METHOD OF FABRICATING A SEMICONDUCTOR

DEVICE USING THE SAME

Mail Stop Amendment Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

## RESPONSE

Sir:

This paper is being filed in response to the Office Action mailed on November 14, 2006.